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(54) **SUPPORT FOR A WAFER FOR FABRICATING A SEMICONDUCTOR**

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(**) Term: **15 Years**

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(30) **Foreign Application Priority Data**

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(51) **LOC (13) Cl.** **13-03**

(52) **U.S. Cl.**
USPC **D13/182**

(58) **Field of Classification Search**
USPC D13/182; D15/144, 144.1; 206/710, 206/711, 712; 118/728, 729, 730, 731, 118/732, 733; 211/41.18; 432/240, 241, 432/253, 258; 156/345.51-345.55
CPC H01L 21/68714; H01L 21/6875; H01L 21/68771; H01L 21/68735; H01L 21/673; H01L 21/67353; H01L 21/67383; C23C 16/458; C23C 16/4581; C23C 16/4582; C23C 16/4583; C23C 16/4584; C23C 16/4587; C23C 16/402; C23C 16/5096; C23C 16/00; C23C 14/50; C23C 14/505; C23C 14/52; C23C 14/54; C23C 14/541; C23C 14/542; C23C 14/548; H01J 27/20; H01J 27/32715; C23F 1/00

See application file for complete search history.

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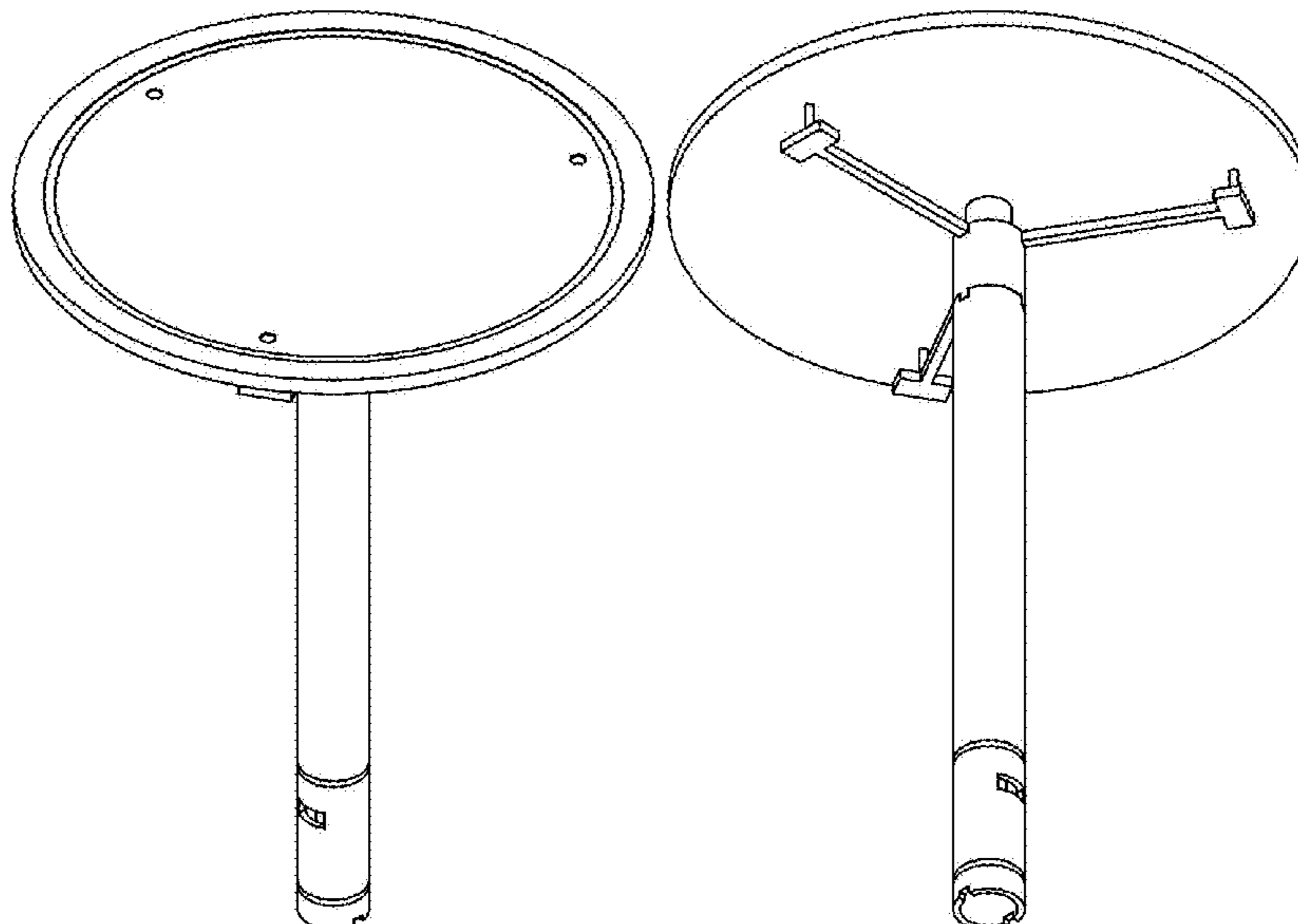
(57) **CLAIM**

The ornamental design for a support for a wafer for fabricating a semiconductor, as shown and described.

DESCRIPTION

FIG. 1 is a front view of a support for a wafer for fabricating a semiconductor showing our new design;
FIG. 2 is a rear view thereof;
FIG. 3 is a top plan view thereof;
FIG. 4 is a bottom plan view thereof;
FIG. 5 is a right side view thereof;
FIG. 6 is a left side view thereof;
FIG. 7 is a top perspective view thereof; and,
FIG. 8 is a bottom perspective view thereof.

1 Claim, 8 Drawing Sheets



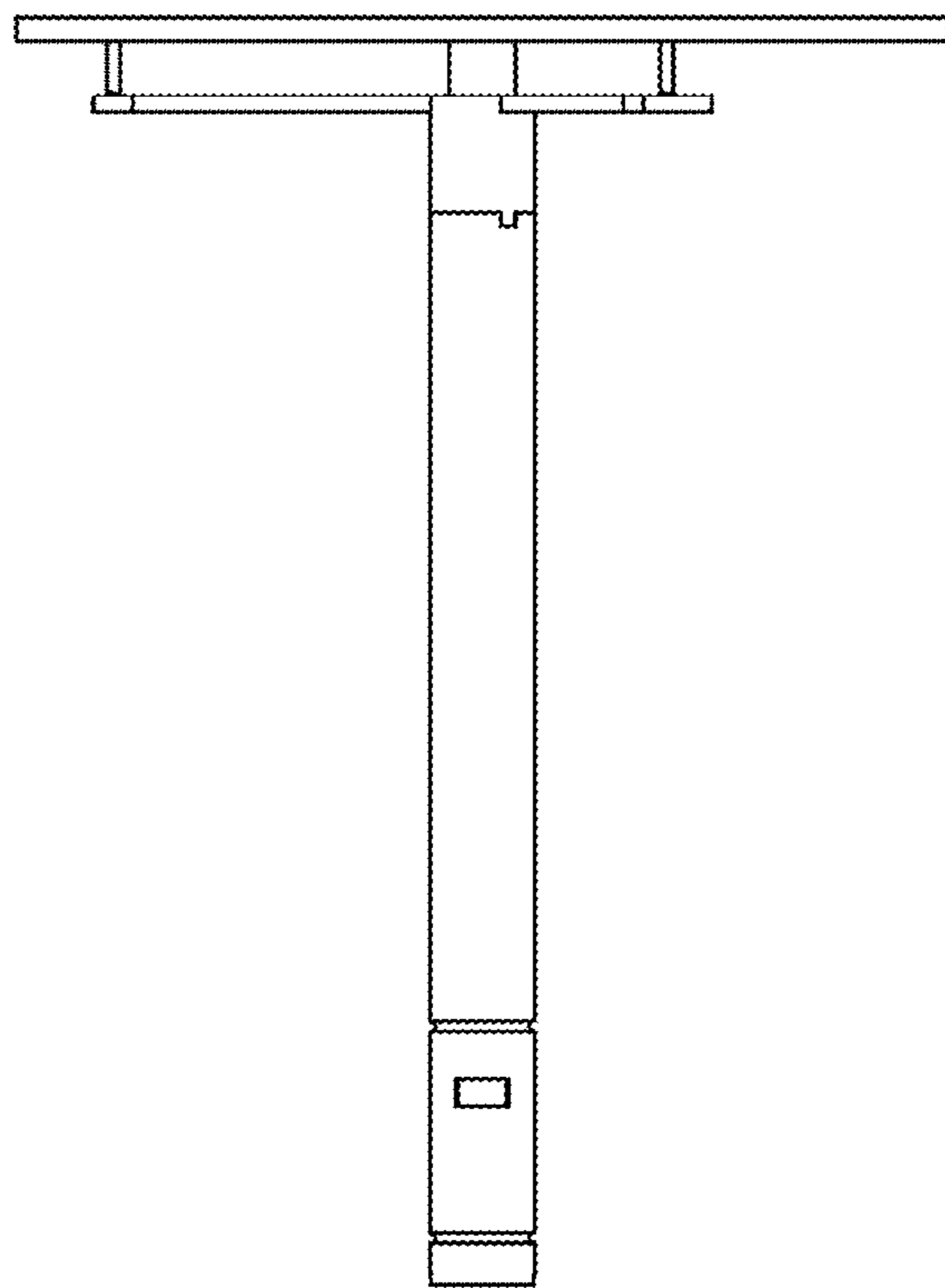


FIG. 1

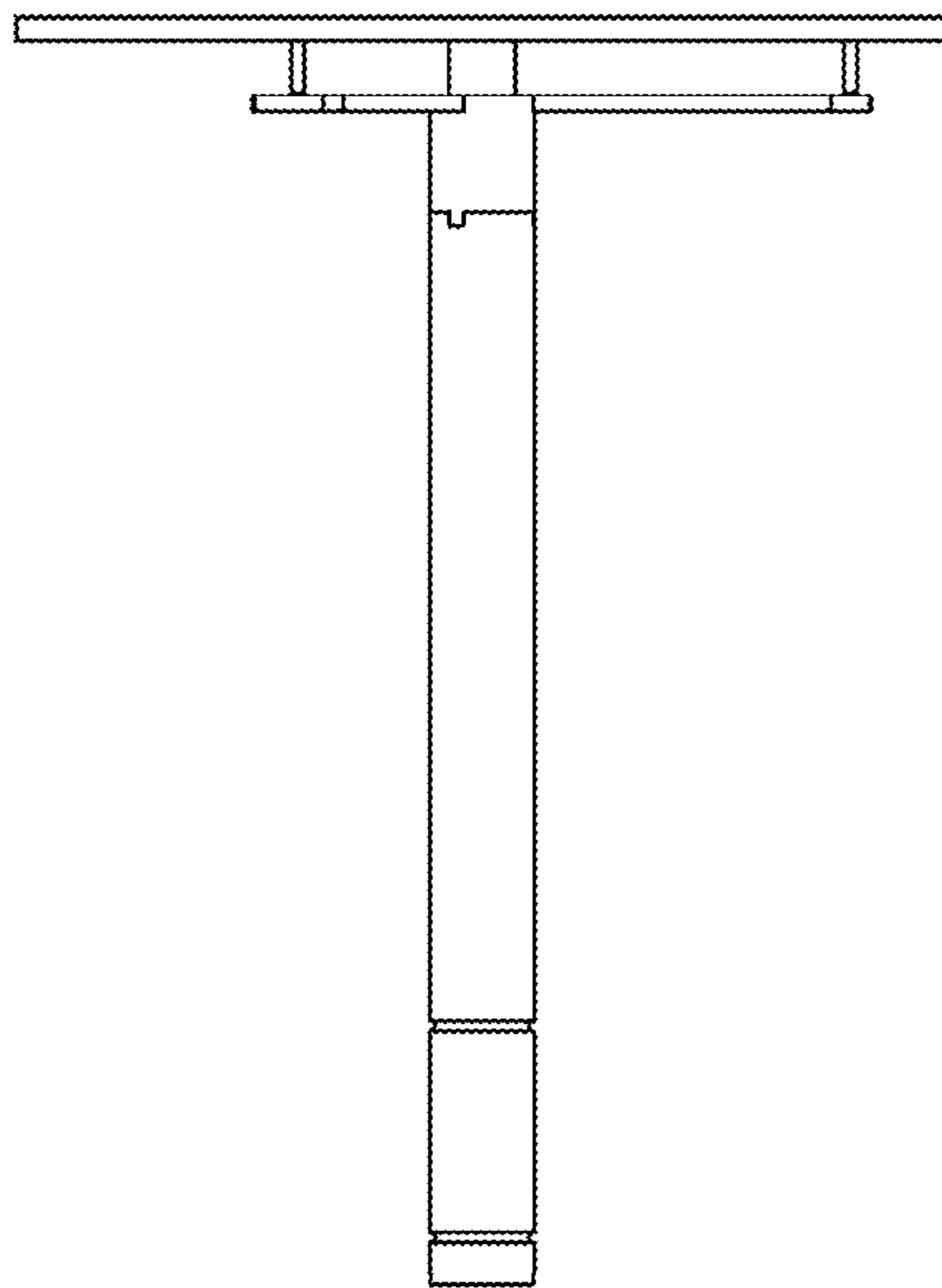


FIG. 2

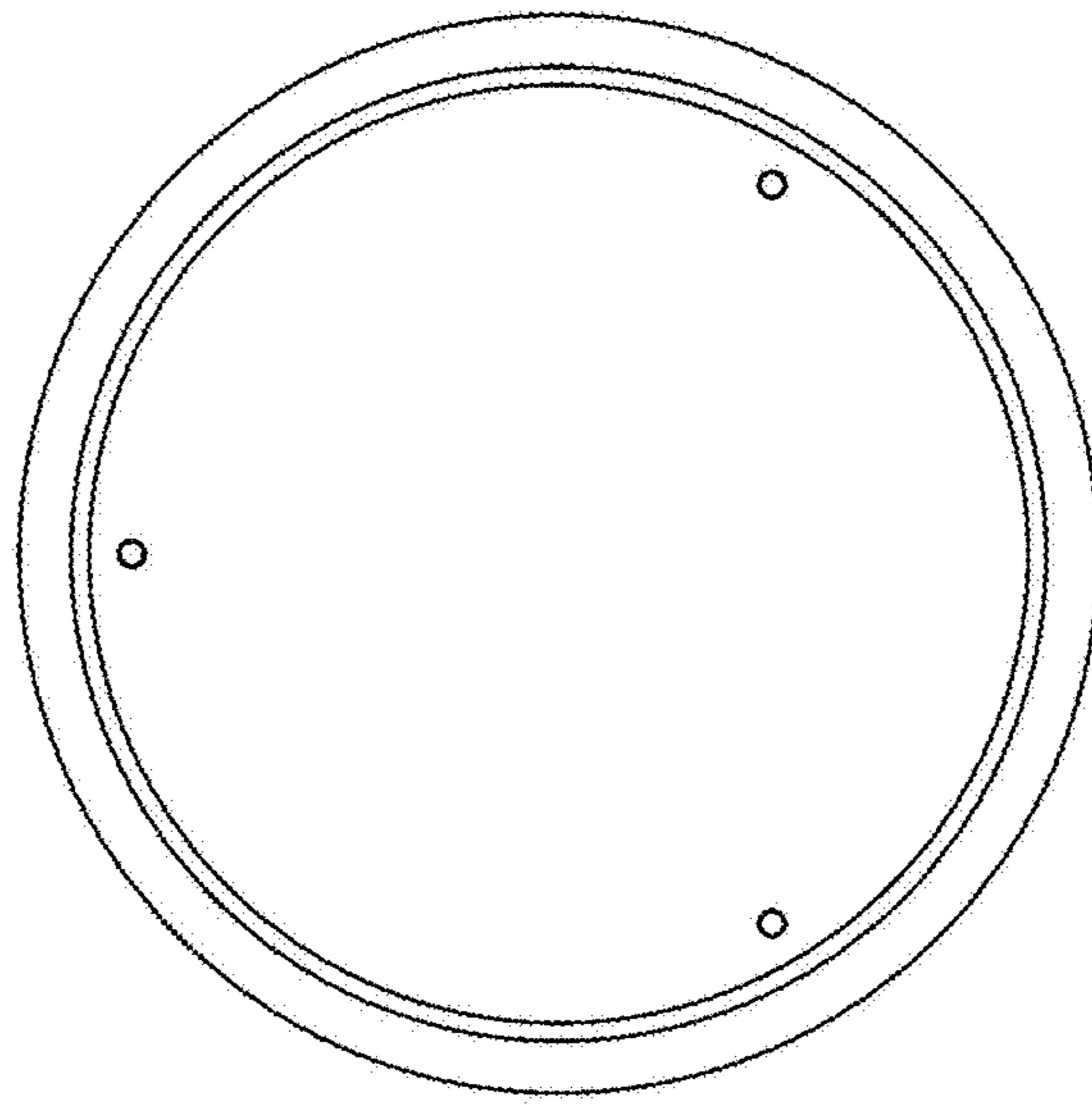


FIG. 3

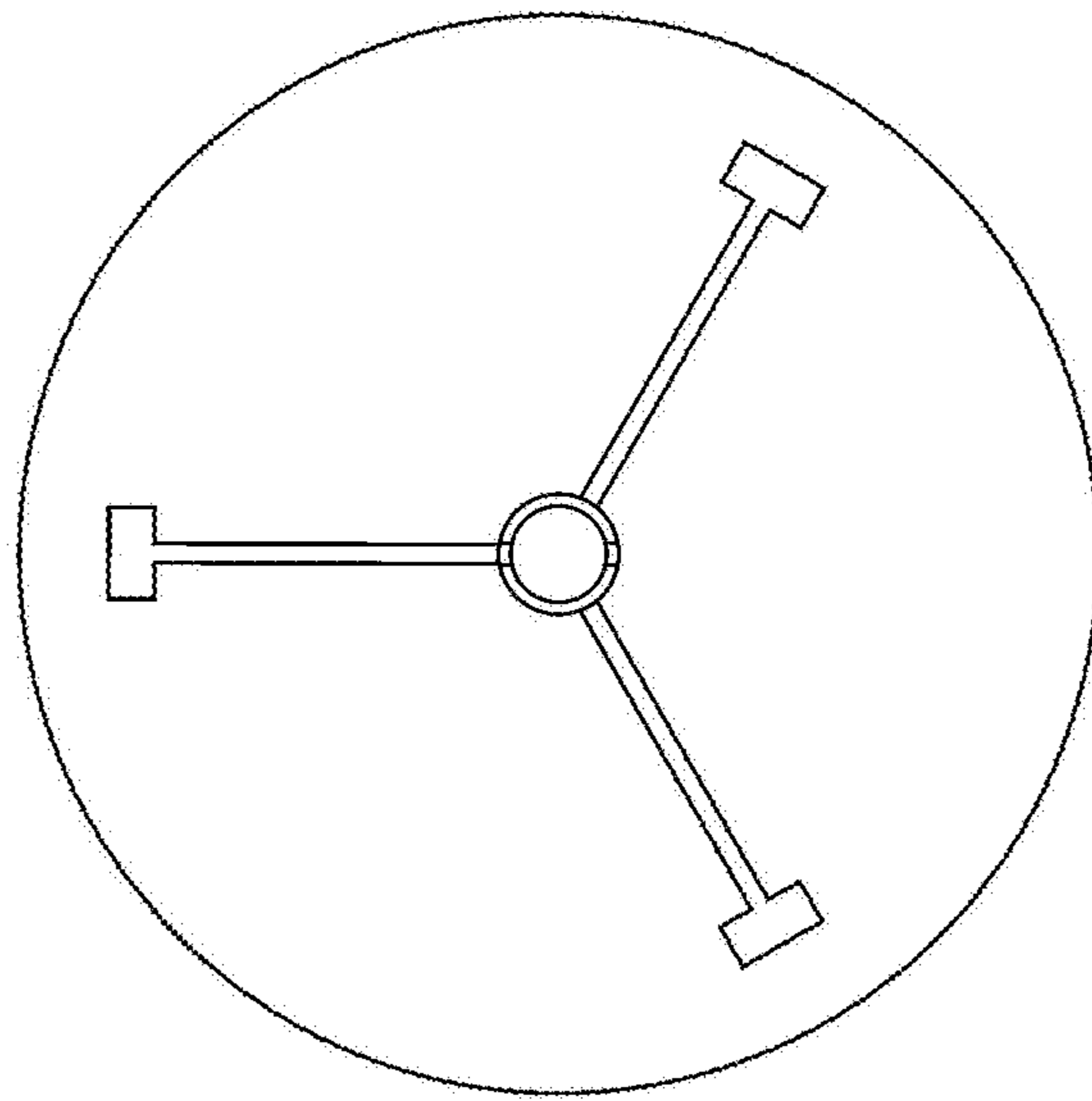


FIG. 4

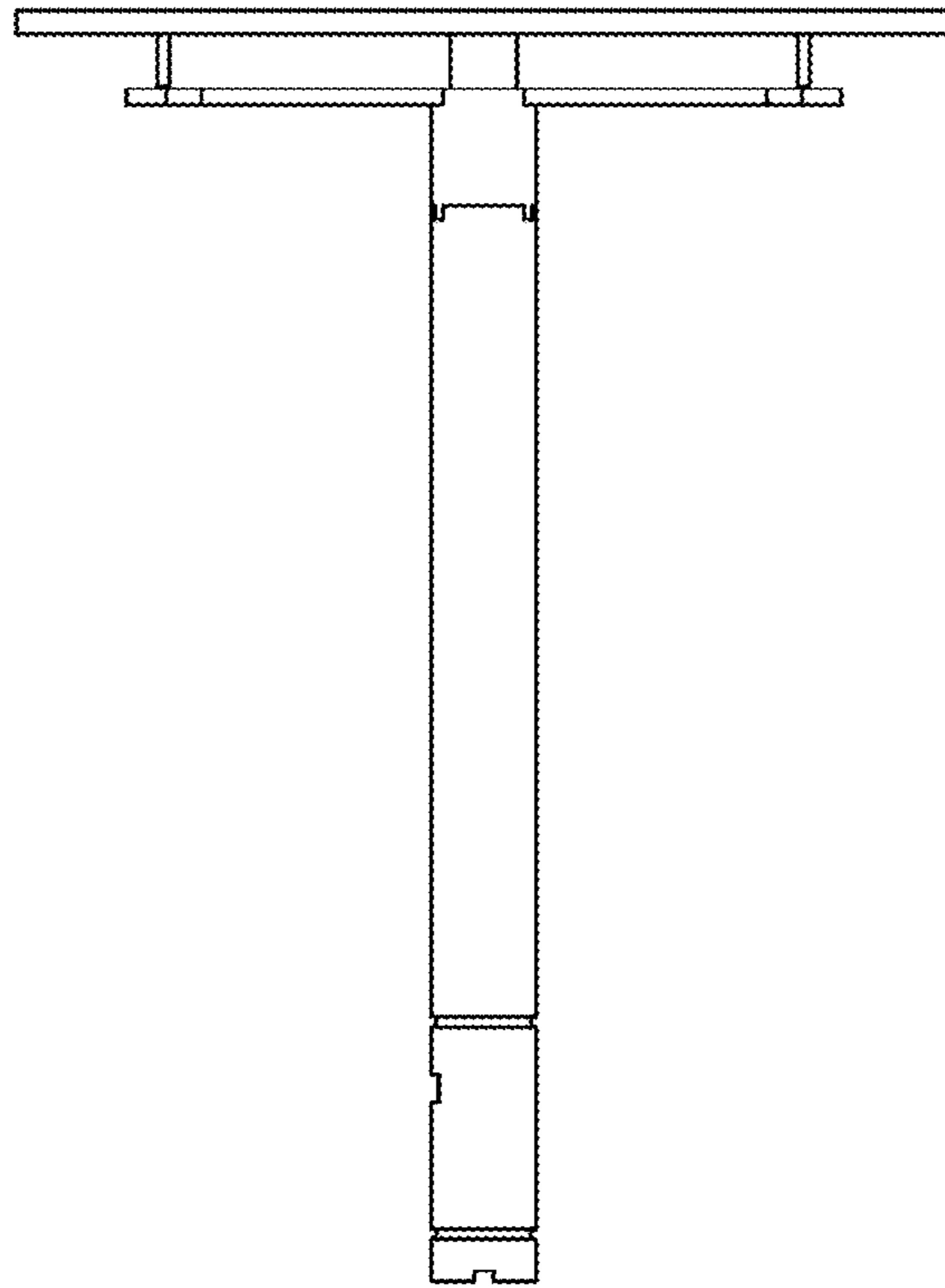


FIG. 5

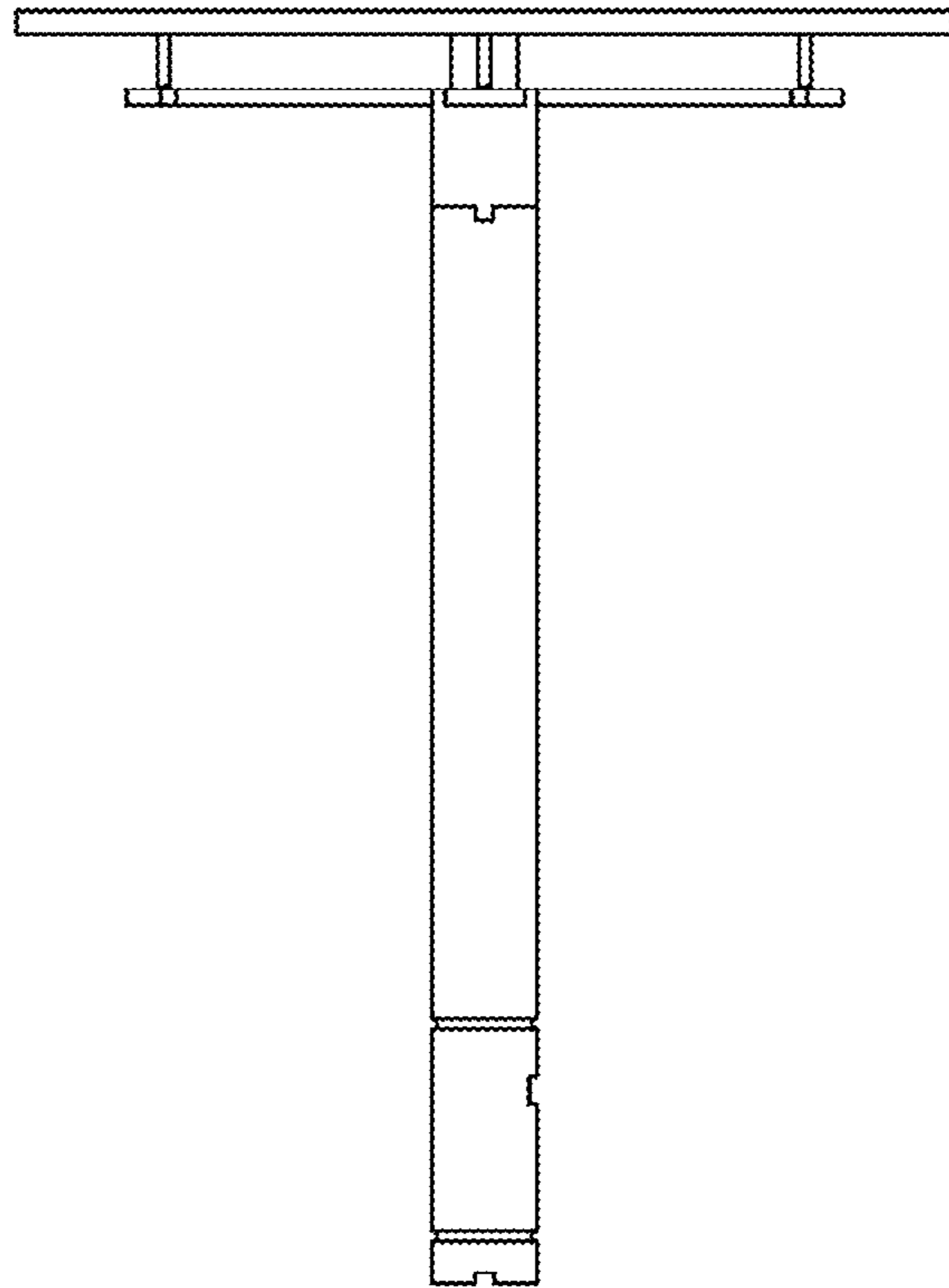


FIG. 6

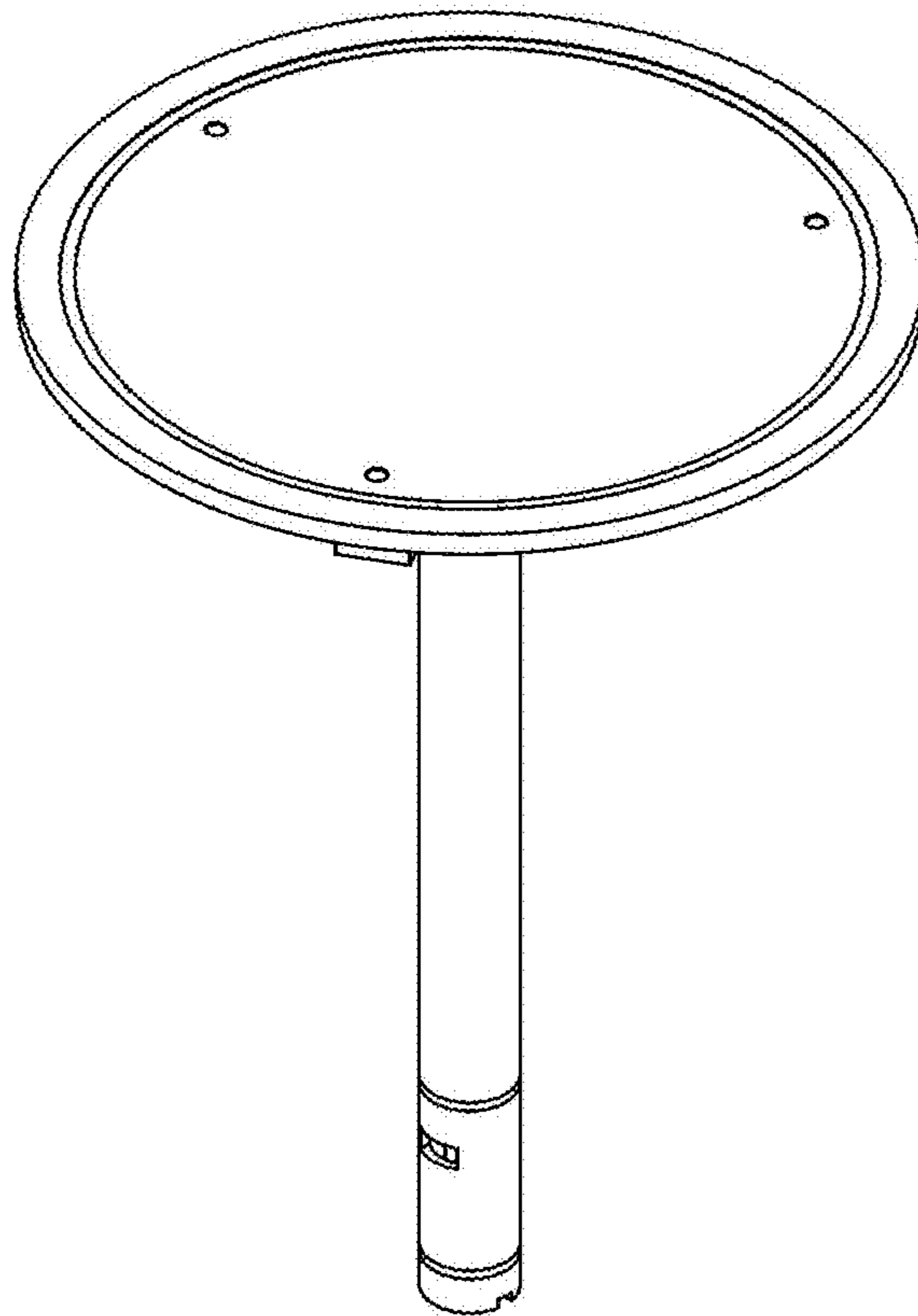


FIG. 7

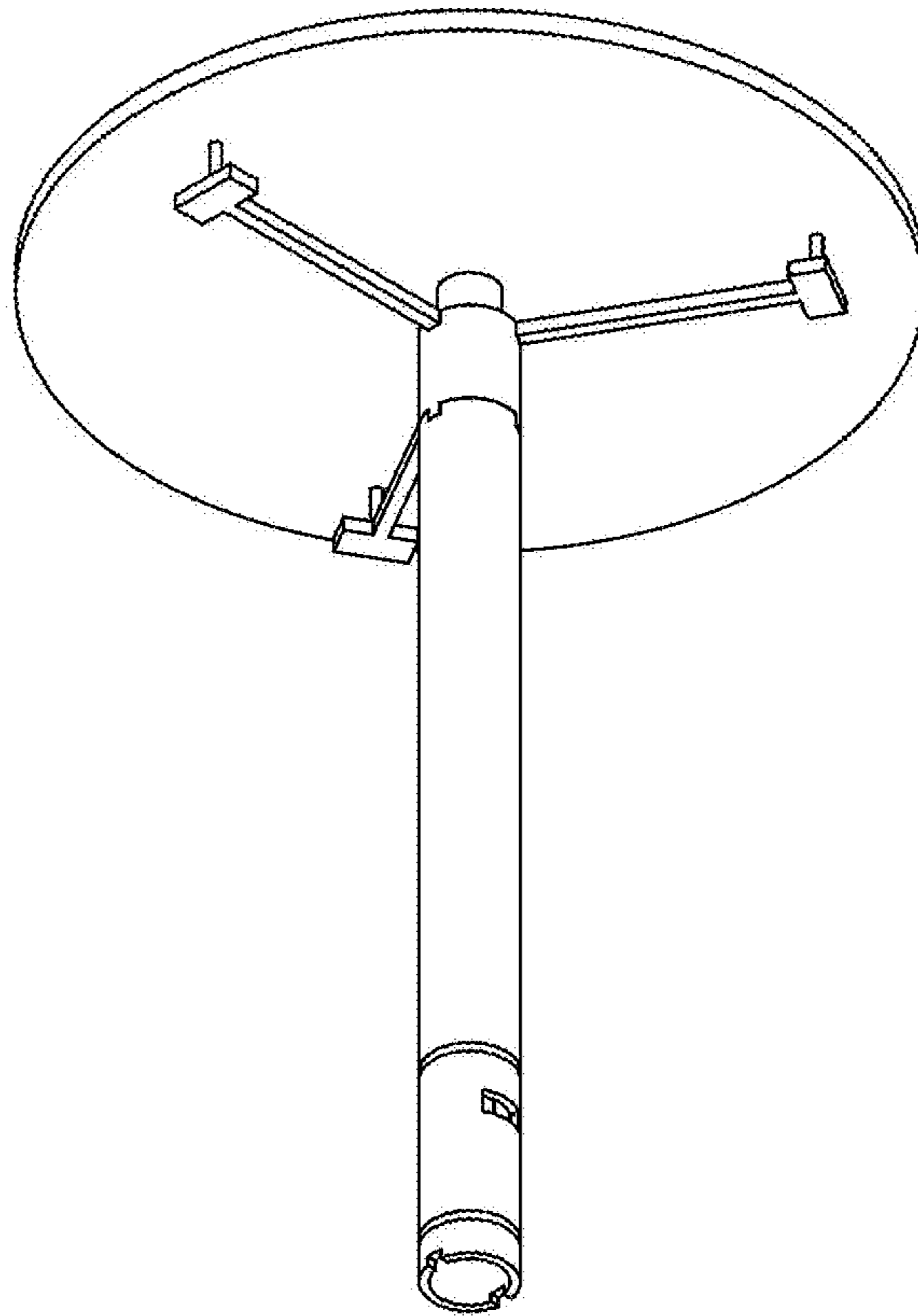


FIG. 8